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Publisher Correction: Stateful characterization of resistive switching TiO₂ with electron beam induced currents

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The original version of this Article contained an error in Eq. 1. The arrows between the symbols "T" and "B", and "B" and "T", were written " \leftrightarrow " but should have been " \rightarrow ", and incorrectly read:

$$I_{\mathrm{EBIC}} = I_{\mathrm{EBAC}} + I_{\mathrm{SEE}} + I_{(\mathrm{e}\leftrightarrow\mathrm{h})} + I_{\mathrm{ISEE}}^{\mathrm{T}\leftrightarrow\mathrm{B}} + I_{\mathrm{ISEE}}^{\mathrm{B}\leftrightarrow\mathrm{T}}$$

The correct from of the Eq. 1 is as follows:

$$I_{\text{EBIC}} = I_{\text{EBAC}} + I_{\text{SEE}} + I_{(e \leftrightarrow h)} + I_{\text{ISEE}}^{\text{T} \to \text{B}} + I_{\text{ISEE}}^{\text{B} \to \text{T}}$$

This has now been corrected in both the PDF and HTML versions of the article.

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